



FORM PTO-1449 (SUBSTITUTE)		Attorney Docket No.: EHF 2001,0167 P	Applic. No. 09/873,230
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		Applicant Norbert Benesch et al.	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (37 CFR 1.98(b))		Filing Date June 4, 2001	Group Art Unit 2621

U.S. PATENT DOCUMENTS

EXAMINER INITIALS		PATENT NO.	DATE	PATENTEE	CLASS	SUB CLASS	FILING DATE
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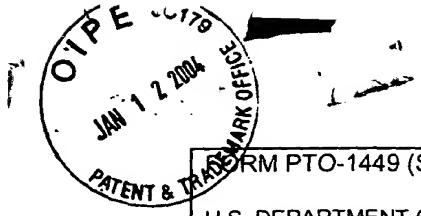
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JS	J	61 169 750	07/31/86	Japan			X
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JS	L	9 191 032	07/22/97	Japan			X
JS	M	9 318 330	12/12/97	Japan			X
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EXAMINER	<i>John Dray</i>	DATE CONSIDERED
		6/16/04

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609;
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Sheet 1 of 3

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT (37 CFR 1.98(b))		Attorney Docket No.: EHF 2001,0167 P	Applic. No. 09/873,230
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

JS	O	M. G. Moharam et al.: "Three-dimensional vector coupled-wave analysis of planar-grating diffraction", J. Opt. Soc. Am., Vol. 73, No. 9, September 1983, pp. 1105-1112
JS	P	M. G. Moharam et al.: "Rigorous coupled-wave analysis of metallic surface-relief gratings", J. Opt. Soc. Am. A, Vol. 3, No. 11, November 1986, pp. 1780-1787

EXAMINER	John Stapp	DATE CONSIDERED
6/16/04		

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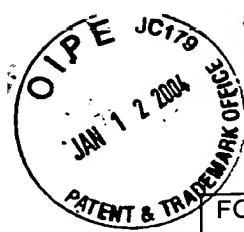
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JS	O	S. S. H. Naqvi et al.: "Etch depth estimation of large-period silicon gratings with multivariate calibration of rigorously simulated diffraction profiles", <i>J. Opt. Soc. Am. A</i> , Vol. 11, No. 9, September 1994, pp. 2485-2493
JS	P	Christopher J. Raymond et al.: "Multiparameter grating metrology using optical scatterometry", <i>J. Vac. Sci. Technol. B</i> , Vol. 15, No. 2, March/April 1997, pp. 361-368
EXAMINER	John Frey	DATE CONSIDERED 6/16/04

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Applicant
Norbert Benesch et al.

Filing Date
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

JS	O	Jörg Bischoff et al.: "New aspects of optical scatterometry applied to microtechnology", SPIE, Vol. 3215, 1997, pp. 144-155
	P	

EXAMINER <i>John Strop</i>	DATE CONSIDERED 6/16/04
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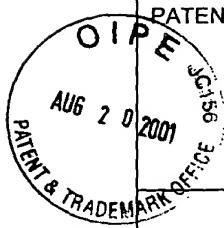
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EXAMINER <i>John Strega</i>	DATE CONSIDERED <i>6/16/04</i>
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U.S. PATENT DOCUMENTS

EXAMINER INITIALS		PATENT NO.	DATE	PATENTEE	CLASS	SUB CLASS	FILING DATE
JS	A	4,964,726	10/23/90	Kleinknecht et al.			
JS	B	5,703,692	12/30/97	McNeil et al.			
JS	C	5,830,611	11/03/98	Bishop et al.			
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JS	J	198 24 624 A1	02/25/99	Germany			X
JS	K	0 874 396 A2	10/28/98	Europe			X
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	M						
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

JS	O	Scott Bushman et al.: "Scatterometry Measurements for Process Monitoring of Polysilicon Gate Etch", SPIE, vol. 32131997, pp. 79-90, XP-000890146
JS	P	Stephen A. Coulombe et al.: "Ellipsometric-Scatterometry for sub-0.1 μm CD measurements", SPIE, vol. 3332, 1998, pp. 282-293, XP-000890148

EXAMINER	John Stacey	DATE CONSIDERED
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June 4, 2001

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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

JS	O	Jörg Bischoff et al.: "Optical scatterometry of quarter micron patterns using neural regression", SPIE, 1998, vol. 3332, pp. 526-537, XP-000890149
JS	P	N. Benesch et al.: Application and cost analysis of scatterometry for integrated metrology", SPIE, vol. 3743, May 1, 1999, pp. 25-32, XP-000890150
EXAMINER	John Stoye	DATE CONSIDERED 6/16/04

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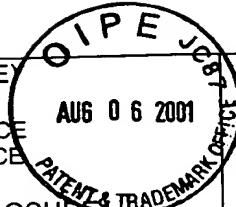
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

JS	O	Michael R. Murnane et al.: "Developed photoresist metrology using scatterometry", SPIE, vol. 2196, March 1994, pp. 47-59, XP-000890152
JS	P	Ikkka Kallioniemi et al.: "Optical scatterometry of subwavelength diffraction gratings: neural-network approach", Applied Optics, vol. 37, No. 25, September 1, 1998, pp. 5830-5835, XP-000890173

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EXAMINER INITIALS		PATENT NO.	DATE	PATENTEE	CLASS	SUB CLASS	FILING DATE
JS	A	5,768,192	06/16/98	Eitan			
JS	B	6,011,725	01/04/00	Eitan			
JS	C	6,191,459 B1	02/20/01	Hofmann et al.			
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	K	196 03 810 C1	08/28/97	Germany			X
	L	195 45 903 A1	06/12/97	Germany			X
	M	196 00 423 A1	07/17/97	Germany			X
	N	WO 99/60631	11/25/99	WIPO			X

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

JS	O	Junko Tanaka et al.: "A Sub-0.1-μm Grooved Gate MOSFET with High Immunity to Short-Channel Effects", IEDM 93, pp. 537-540;
JS	P	Ken-ichiro Nakagawa et al.: "A Flash EEPROM Cell with Self-Aligned Trench Transistor & Isolation Structure", 2000 Symposium on VLSI Technology Digest of Technical Papers

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